

2020년 2월 13일(목), 10:45~12:30

Room K (다이아몬드 I, 6층)

**D. Thin Film Process Technology 분과**  
**[TK2-D] Thin Film Process II**

<p>TK2-D-1 10:45~11:15</p>	<p>[초청] <b>Strategies for Stabilization of Metastable Phases in Atomic Layer Deposition</b> Seong Keun Kim <i>Center for Electronic Materials, KIST</i></p>
<p>TK2-D-2 11:15~11:30</p>	<p><b>Hollow Cathode Plasma Source를 이용한 고품질 SiN ALD 공정</b> Jae Chan Park<sup>1</sup>, Dae Hyun Kim<sup>2</sup>, Tae Jun Seok<sup>1</sup>, Dae Woong Kim<sup>1</sup>, Woo-Hee Kim<sup>1</sup>, and Tae Joo Park<sup>1,2</sup> <sup>1</sup><i>Department of Materials Science and Chemical Engineering, Hanyang University,</i> <sup>2</sup><i>Department of Advanced Materials Engineering, Hanyang University</i></p>
<p>TK2-D-3 11:30~11:45</p>	<p><b>Low-temperature Atomic Layer Deposition of Silicon Nitride Film Using Silicon Halide Precursors</b> 신종우<sup>1</sup>, 문찬희<sup>1</sup>, 하제영<sup>1</sup>, 유능경<sup>2</sup>, 송봉근<sup>2</sup>, 이한보람<sup>1</sup> <sup>1</sup><i>인천대학교 신소재공학과, <sup>2</sup>홍익대학교 화학공학과</i></p>
<p>TK2-D-4 11:45~12:00</p>	<p><b>N<sub>2</sub>H<sub>4</sub>를 이용한 저온 Thermal ALD SiN 박막 공정</b> Jae Chan Park<sup>1</sup>, Dae Hyun Kim<sup>2</sup>, Tae Jun Seok<sup>1</sup>, Dae Woong Kim<sup>1</sup>, Woo-Hee Kim<sup>1</sup>, and Tae Joo Park<sup>1,2</sup> <sup>1</sup><i>Department of Materials Science and Chemical Engineering, Hanyang University,</i> <sup>2</sup><i>Department of Materials Science and Chemical Engineering, Hanyang University</i></p>
<p>TK2-D-5 12:00~12:15</p>	<p><b>Growth Behavior and Properties of Ru Film by Electric Field/Potential Assisted Atomic Layer Deposition (EA-ALD)</b> Ji won Han and Tae Joo Park <i>Department of Materials Science and Chemical Engineering, Hanyang University</i></p>
<p>TK2-D-6 12:15~12:30</p>	<p><b>Improvement in the Surface Morphology of the Bottom Ru Electrode for DRAM Capacitor</b> Dae Seon Kwon, Dong Gun Kim, Junil Lim, Tae Kyun Kim, Haeng Ha Seo, and Cheol Seong Hwang <i>Department of Materials Science and Engineering and Inter-University Semiconductor Research Center, Seoul National University</i></p>